External_Type	Material_Group	Substances	CAS_Number	Mass	Mass_Percentage_in_Leaf	Massmg
Die	Metal oxide	Lead Dioxide (PbO2)	1309-60-0	0.00162	0.66	0.09702
	Doped silicon	Silicon (Si)	7440-21-3	0.24392	99.34	14.60298
			Subtotal	0.24554	100	14.7
Post-plating	Lead alloy	Tin (Sn)	7440-31-5	0.45433	100.0	27.2
			Subtotal	0.45433	100	27.2
Lead Frame	Copper alloy	Phosphorous (P)	7723-14-0	0.02005	0.03	1.20057
	Copper alloy	Iron (Fe)	7439-89-6	0.06684	0.1	4.0019
	Copper alloy	Copper (Cu)	7440-50-8	66.7576	99.87	3,996.69753
			Subtotal	66.84449	100	NaN
Mould Compound	Polymer	Phenol Formaldehyde resin (generic)	9003-35-4	2.0939	6.5	125.359
	Polymer	Epichlorohydrin/o- Cresol/Formaldehyde polymer (generic)	29690-82-2	5.1542	16.0	308.576
	Filler	Silica fused	60676-86-0	22.87178	71.0	1,369.306
	Flame retardant	Metal hydroxide		2.0939	6.5	125.359
			Subtotal	32.21378	100	NaN
Solder Wire	Lead alloy	Tin (Sn)	7440-31-5	0.00458	5.0	0.274
	Lead alloy	Silver (Ag)	7440-22-4	0.00229	2.5	0.137
	Lead alloy	Lead (Pb)	7439-92-1	0.08467	92.5	5.069
			Subtotal	0.09154	100	5.48
Wire	Pure metal	Aluminium (AI)	7429-90-5	0.15033	100.0	9
			Subtotal	0.15033	100	9
			Total	100.00001	100	NaN

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